

Title (en)

MODULATED POWER FOR IONIZED METAL PLASMA DEPOSITION

Title (de)

PLASMA-GASPHASENABSCHIEDUNG MITTELS MODULIRTER SPULENZERSTÄUBUNGSLEISTUNG FÜR IONISIERTE METALLPLASMAABSCHIEDUNG

Title (fr)

MODULATION DE COURANT POUR DEPOT AU PLASMA DE METAL IONISE

Publication

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Application

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Priority

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Abstract (en)

[origin: WO9907913A1] In a plasma deposition system for depositing a film of sputtered target material on a substrate, the output of an RF generator coupled to a coil for generating a plasma can be varied during the deposition process so that heating and sputtering of the RF coil can be more uniform by "time-averaging" RF voltage distributions along the RF coil. In another embodiment, RF energy applied to a coil positioned to sputter material onto a workpiece, is modulated to control the biasing of the coil. As a consequence, control of coil sputtering may be improved such that the uniformity of deposition may also be improved.

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IPC 8 full level

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CPC (source: EP KR)

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See references of WO 9907913A1

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